

VLSI Design

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2016/03/22

Outline

1. Element Design Guides
2. Process Errors and Matched Layout
3. Switch Characteristics
4. CMOS Gate Transistor Sizing
5. Power Dissipation
6. Conductor Sizing
7. Charge Sharing
8. Design Margining
9. Yield

Channel Sheet Resistance

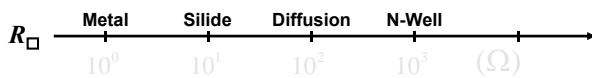
- Linear Region: VCR (Voltage Control Resistance) Region.

Linear Region:
$$I_{DS} = \beta \left[(V_{GS} - V_t)V_{DS} - \frac{V_{DS}^2}{2} \right]$$

$$R \equiv \frac{\delta V_{DS}}{\delta I_{DS}} = \frac{1}{\mu C_{ox}(V_{GS} - V_t - V_{DS})} \cdot \frac{L}{W} \approx \frac{1}{\mu C_{ox}(V_{GS} - V_t)} \cdot \frac{L}{W}$$

Channel Sheet Conductance $\sigma_s \approx \mu C_{ox}(V_{GS} - V_t)$

- Approximate Orders in about 2000's Technologies:



Approximate Intrinsic MOS Gate C_{\square}

$C_g =$

Region Portion	Cut-off	Linear	Saturated
C_{gb}	$\frac{\epsilon A}{t_{ox}}$	0	0
C_{gs}	0	$\frac{\epsilon A}{2t_{ox}}$	$\frac{2\epsilon A}{3t_{ox}}$
C_{gd}	0	$\frac{\epsilon A}{2t_{ox}}$	0

$$C_{\square} = 1 \sim 10 \text{ fF}/\mu\text{m}^2$$

Element Design Guide

Resolution/Error

- **Spiral Inductance:** > 10%
- **Resistance:** about 5% ~ 10%
- **Poly-capacitance:** about 1%
- **Error cancellation** is usually used to reduce the error from about 10% to 1%.
- **Fit the range in non-critical circuit then take care of the resolution in critical circuit.**

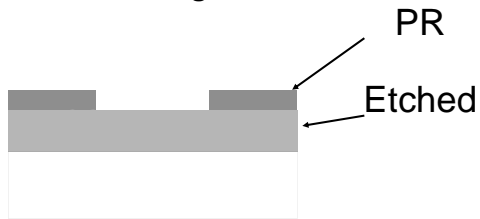
Process Error

Process Error

- **Geometrical Factor**
 - XY-Plane: Shifting
 - Z-Plane: usually radial to the aperture
- **Non-Geometrical Factor**
 - Density, temperature, duration, defect, etc.

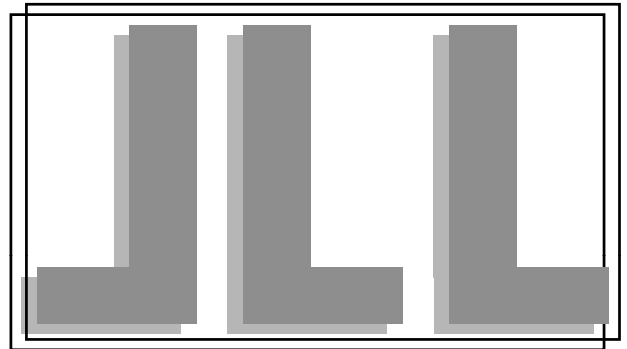
Geometrical Errors

1. Radical factor : e.g.,

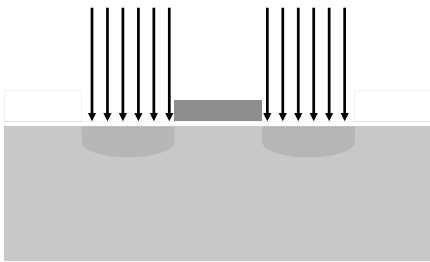


Geometrical Errors

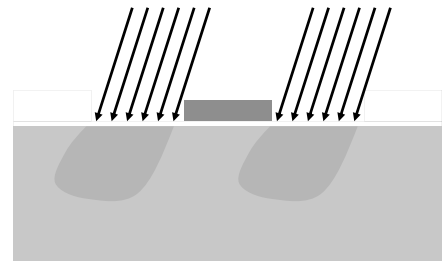
2. Shifting : e.g.,



Optimized Angle of Iron Implant

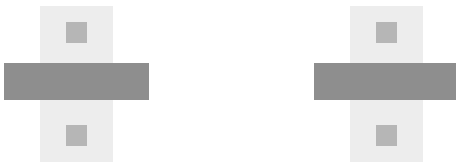


Optimized Angle of Iron Implant



The implant parameters and the yield will be traded off.

Matching



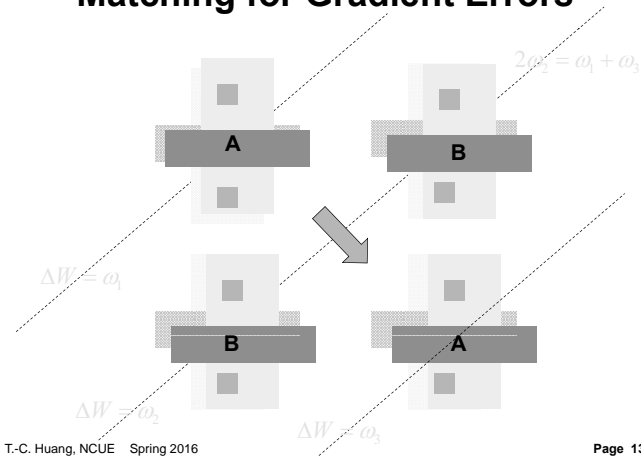
Matching for Constant Errors



$$\frac{w+\Delta w}{L+\Delta L}$$

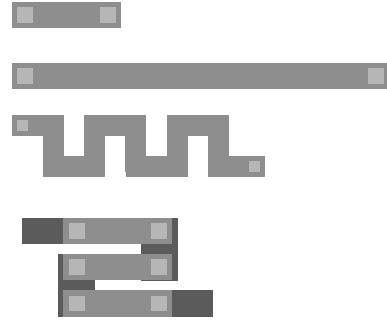
$$\frac{w+\Delta w}{L+\Delta L}$$

Matching for Gradient Errors



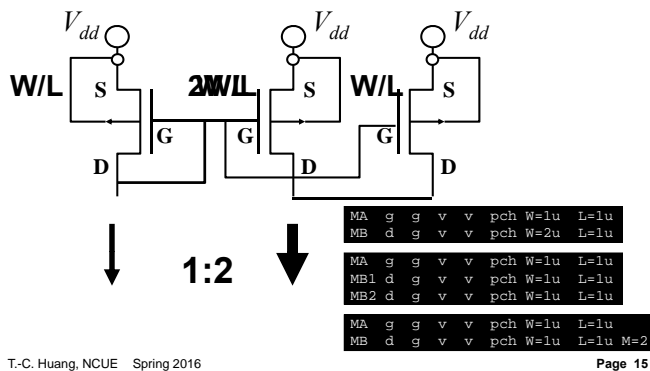
Ratio-Matching

1. Duplication :



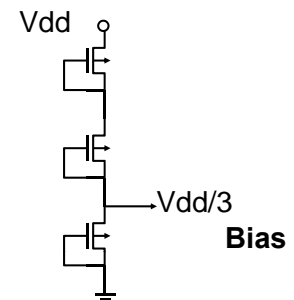
Ratio-Matching

2. E.g., Current repeater:



Ratio-Matching

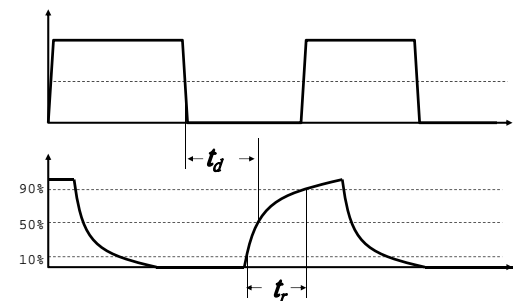
3. E.g., Voltage divider :



Switching Timing Parameters

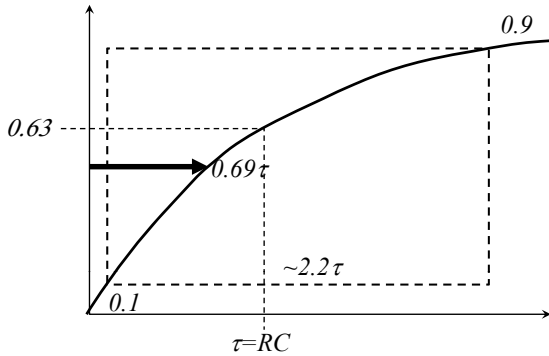
1. Rise Time: $0.1V_{dd} \rightarrow 0.9V_{dd}$
2. Fall Time: $0.9V_{dd} \rightarrow 0.1V_{dd}$
3. Delay: $0.5V_{dd}$ Input \rightarrow $0.5V_{dd}$ Output
??? for a single gate or with a cascade delay line ?
4. Propagation Time :
Input change starting \rightarrow Output steady
5. Settling Time:
Change starting \rightarrow (Error < allowance)
Note to justify for given premise.

Switching Timing Parameters



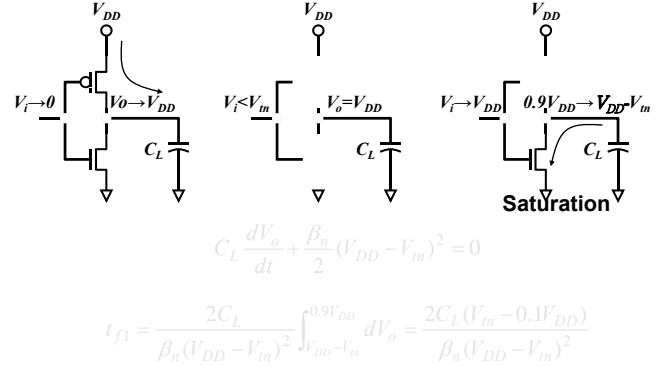
Switch Characteristics

Step Response of an RC Circuit



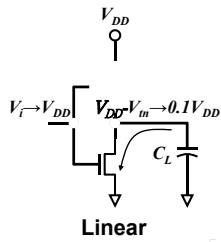
Switch Characteristics

Analytic Delay Model



Switch Characteristics

Analytic Delay Model



Let $n = \frac{V_{in}}{V_{DD}}$

$$t_{f2} = \frac{C_L}{\beta_n (V_{DD} - V_{in})} \int_{0.1V_{DD}}^{V_{DD} - V_{in}} \left[\frac{1}{\frac{V_o^2}{2(V_{DD} - V_{in})} - V_o} \right] dV_o = \frac{C_L}{\beta_n V_{DD} (1-n)} \ln(19-20n)$$

Switch Characteristics

Analytic Delay Model

$$t_f = t_{f1} + t_{f2} = \frac{2C_L}{\beta_n (V_{DD} - V_{in})} \left[\frac{n-0.1}{1-n} + \frac{\ln(19-20n)}{2} \right], \text{ where } n = \frac{V_{in}}{V_{DD}}$$

$$t_f \approx k \frac{C_L}{\beta_n V_{DD}}, \text{ where } k \approx 3 \dots 4$$

$$t_r = t_{r1} + t_{r2} = \frac{2C_L}{\beta_p (V_{DD} - V_{tp})} \left[\frac{p-0.1}{1-p} + \frac{\ln(19-20p)}{2} \right], \text{ where } p = \frac{V_{tp}}{V_{DD}}$$

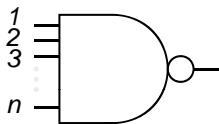
$$t_r \approx k \frac{C_L}{\beta_p V_{DD}}, \text{ where } k \approx 3 \dots 4$$

Equal rise/fall time inverter size: $\beta_p = \beta_n$

Approximate average gate delay: $t_d \approx (t_r + t_f) / 2$

Switch Characteristics

Delays in a Compound Gate



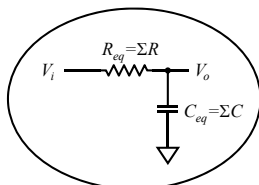
Given a $(n-1)$ -tuple pattern, there exists a set of rise/fall/delay times.

Transistor-Level Models

No	Model	Nmemonics	Examples
1	Switch	$R_{off} = \text{infin.}$	$M1 \text{ on} \rightarrow M2 \text{ off} \rightarrow V_o = V_{DD}$
2	Stack Effect	$R_s = \sum R_i$	Wafer Power, Equivalent R
3	RC Model	$\tau = RC$	$T_r = 2.2\tau, t_d = 0.69\tau, f = 1/2\pi\tau$
4	Toggle Rate	$P_d = ka$	$a = \text{switching activity}$
5	EI More Model	$\tau = \sum (RC)_{loop}$	Intrinsic Delay, T_r, T_d, P_d , gate parameters
6	Rabaey's Logical Effort	$i + bl$	P_d, T_p of gate-level circuits
7	Shocklay	1 st Order Eq.	See Lec.3
8	SPICE II	-	See Lec.4
9	BSIM	-	Refer to <i>ucb</i>

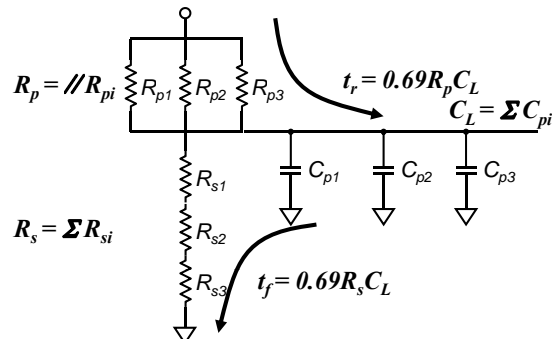
Switch Characteristics

Worst-Case RC Model

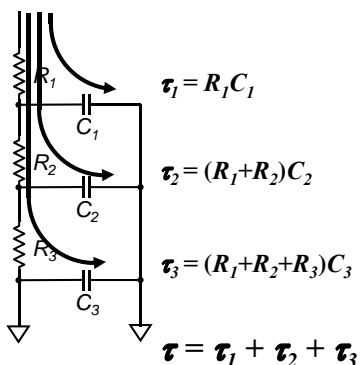


Time Constant = $\tau < R_{eq}C_{eq}$

Simple RC Model – Stack Effect

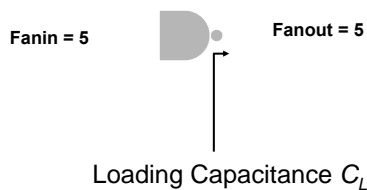


Elmore Delay Model



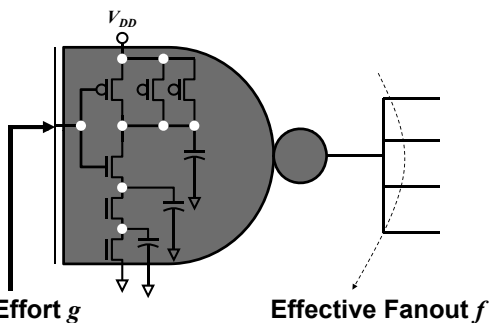
Switch Characteristics

Loading



Efforts of Gate Delay

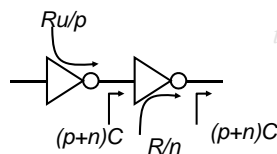
$t_d = gf + d_o$



Gate Transistor Sizing

Cascade CMOS Inverters

For an inverter with $L_p=L_n=L_{min}$, and $W_p=pW_{min}$, $W_n=nW_{min}$,
 Let $C=C_L$ when $W_p=W_n=W_{min}$,
 $R=R_n$ when $W_p=W_n=W_{min}$ and $\mu_p:\mu_n=1$

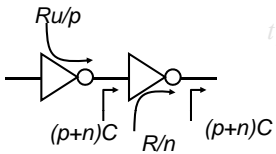


$t_{inv-pair} = (\frac{u}{p} + \frac{1}{n})(p+n)RC$

If $u=2$, then it has the same delay for $p=n$ and $p=2n$.

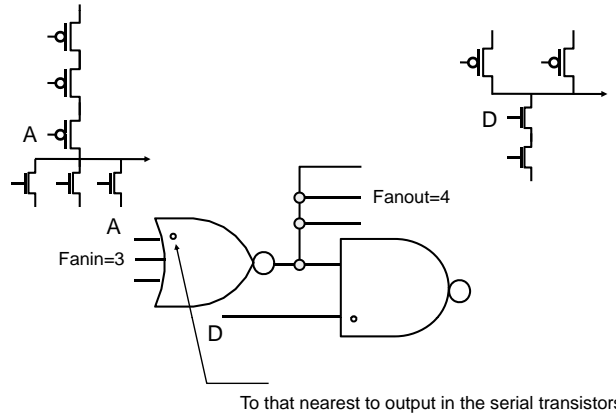
Gate Transistor Sizing Cascade Psuedo-NMOS Inverters

For equivalent noise margin (ENM) pseudo-NMOS inverters:
 $\beta_n/\beta_p \sim 6$, such that $n=3p$ is usually chosen.



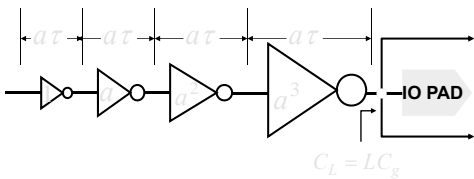
$$t_{inv-pair} = \left(\frac{u}{p} + \frac{1}{n}\right)(p+n)RC$$

Fan-In and Fan-Out



Gate Transistor Sizing

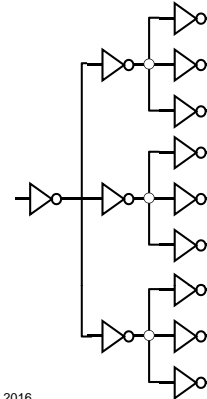
Stage Ratio a



Total delay = $na\tau = \frac{\ln(L)}{\ln(a)} a\tau$ To minimize $\frac{a}{\ln(a)}$, we have $a = e \approx 2.72$

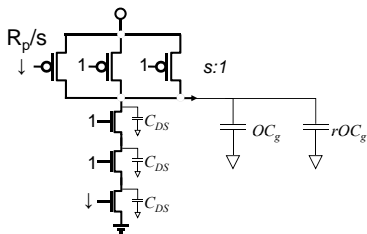


Clock Tree using Standard Cells with a Stage Ratio 3



Transistor Stage-Ratio Principle

Assume size: s , $C_{DS} = dC_g$, $C_{1-route} = rC_g$ and $Fanin = 1$, $Fanout = 0$



$$t_r = (R_p/s)[(sld+rO+O)C_g]$$

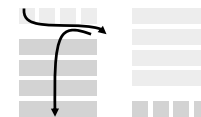
$$t_f = (IR_n/s)[(sld+rO+O)C_g]$$

output part
internal part

Transistor Stage-Ratio Principle Equal Rise/Fall Time Design

If $t_r = t_f$, $\mu_p W_p = I \mu_n W_n$ for NAND gates

$I \mu_p W_p = \mu_n W_n$ for NOR gates.



Normalized-mobility
Usually, $I \approx 2 \dots 5$

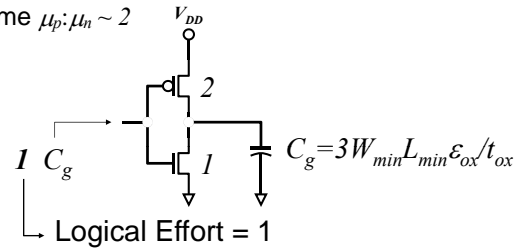
Transistor Stage-Ratio Principle

High-Speed Design Guideline

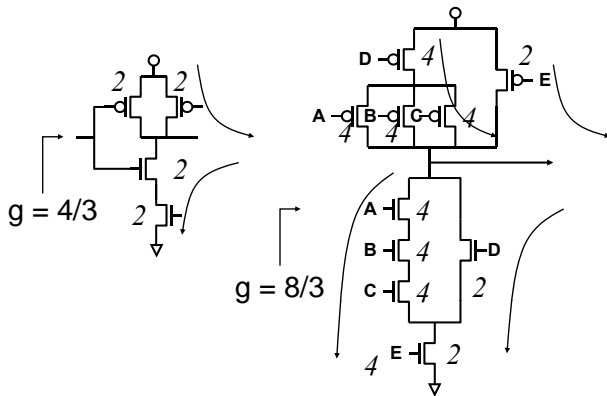
1. Use NAND instead of NOR gates
2. Place inverters at high-fanout nodes
3. Fanin < 5; Fanout < 10
4. Use min.-sized gates on high-fanout nodes;
5. Keep Rise/Fall edges sharp

Logical Efforts

- Usually, select input capacitance C_g , turn-on resistance R_{on} as units.
- Mark the transistor widths in units W_{min} when all L 's = L_{min}
- Assume $\mu_p: \mu_n \sim 2$

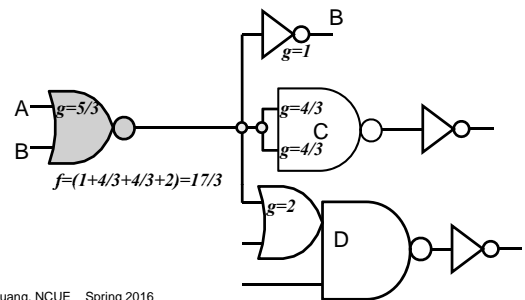


Examples for Logical Efforts



Effective Fanout f

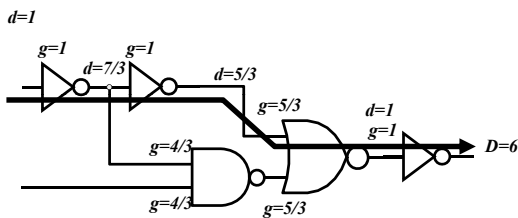
Neglecting intrinsic delay, $t_{i1}=1$ $f=1$ $g=1$ Named as invhx
 Assume the unitary inverter has a half drive for driving 2 inverters.



Example: Unitary-Drive Design

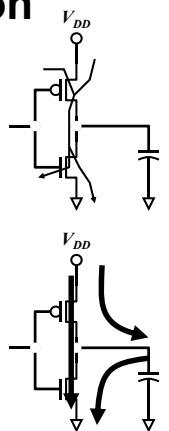
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 Assume the unitary inverter has a half drive for driving 2 inverters.

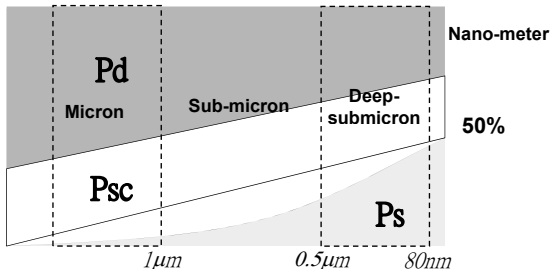


Power Dissipation

- Static Power Dissipation
- Dynamic Power Dissipation
 - Switching Transient (Short-circuit) Current
 - Charging/Discharging of C_L



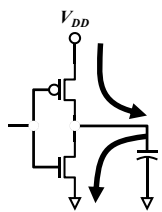
Power Dissipation



Power Dissipation Static Dissipation

- **Quiescent State**
 - Input steady for enough time
 - Either P- or N- Network is off
 - Theoretically, $IDDQ \rightarrow 0$
- However, small static dissipation due to
 - Reverse bias leakage I_{SB}
 - Gate leakage
- Considerable in deep submicron era

Power Dissipation Dynamic Dissipation



$$P_d = \frac{1}{T} \left[\int_0^{T/2} i_n(t) V_o dt + \int_{T/2}^T i_p(t) (V_{DD} - V_o) dt \right]$$

$$\therefore i(t) dt = C dV$$

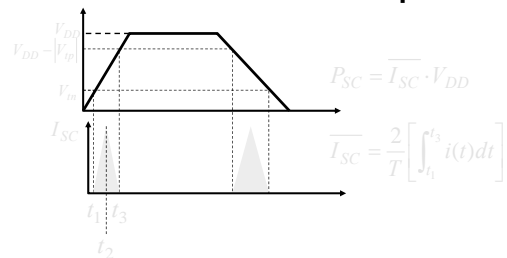
$$\therefore P_d = C_L V_{DD}^2 f_p$$

Note f_p is a repetition frequency

For CMOS Logic Circuits with switching activity a , select circuit frequency $f = af_p$;

$$P_d = \frac{1}{2} a f C_L V_{DD}^2$$

Power Dissipation Short-Circuit Dissipation



$$P_{SC} = \overline{I_{SC}} \cdot V_{DD}$$

$$\overline{I_{SC}} = \frac{2}{T} \left[\int_{t_1}^{t_3} i(t) dt \right]$$

Under linear approximation $t_r = t_f = rT$ and $V_m = |V_{tp}| = V_t$,

$$P_{SC} = \frac{\beta r}{12} (V_{DD} - 2V_t)^3$$

Over-dissipation

1. Conductor Damage

1. Metal Migration

1. $J < J_{max}$ ← Contact Replication
2. Temperature
3. Crystal structure

2. Noise & Crosstalk

3. RC Delay

2. Ground (Power) Bounce

1. Performance Impact

2. Failure

Measurement in HSPICE

- TRAN 1PS 1US
- MEAS TRAN P1 AVG POWER FROM=10NS TO=40NS
- MEAS TRAN P2 RMS POWER
- MEAS TRAN T1 TRIG V(IN) VAL=2.5 RISE=1
- + TARG V(OUT) VAL=2.5 FALL=1

In file.lis, you can find the report of P1, P2, and T1.